L Number	Hits	Search Text	DB	Time stamp
26	100	(isolation same gate same (source or drain	USPAT;	2004/09/17
		or source/drain) same (insulation or	US-PGPUB;	22:11
		insulating or dielectric) same silicide).clm.	EPO; JPO;	
		,	DERWENT;	
	`	*	IBM_TDB	
28	328	(isolation same gate same (source or drain	USPAT;	2004/09/17
		or source/drain) same (insulation or	US-PGPUB;	22:11
		insulating or dielectric) same silicide same	EPO; JPO;	
		sidewall same spacer)	DERWENT;	
		,	IBM_TDB	
27	40	(isolation same gate same (source or drain	USPAT;	2004/09/17
		or source/drain) same (insulation or	US-PGPUB;	22:12
		insulating or dielectric) same silicide same	EPO; JPO;	
		sidewall same spacer).clm.	DERWENT;	•
	•	,	IBM TDB	
29	1	(isolation same gate same (source or drain	USPAT;	2004/09/17
	•	or source/drain) same (insulation or	US-PGPUB;	22:12
,		insulating or dielectric) same silicide same	EPO; JPO;	
		sidewall same spacer).clm. and choi	DERWENT;	
		ciacinali camo opaconyionini ana cinci	IBM_TDB	
30	57	blocking adj insulation	USPAT;	2004/09/17
	٠.	biooking any monation	US-PGPUB;	22:12
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
31	225	(blocking adj (insulating or dielectric or	USPAT;	2004/09/17
		insulation))	US-PGPUB;	22:13
		insulation,,	EPO; JPO;	22.13
			DERWENT;	
			IBM_TDB	
32	2	((blocking adj (insulating or dielectric or	USPAT;	2004/09/17
J2	_	insulation)) with isolation) same (silicide)	US-PGPUB;	22:14
		modulation,, with toolation, bame (binotae)	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
33	4	(blocking adj (insulating or dielectric or	USPAT;	2004/09/17
	_	insulation)).clm. and isolation.clm. and	US-PGPUB;	2004/09/17 22:15
		silicide.clm.	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
34	1143	silicide.clm. and isolation.clm. and	USPAT;	2004/09/17
-		(insulating or insulator or insulation or	US-PGPUB;	22:16
		dielectric .clm.	EPO; JPO;	22.10
			DERWENT;	
			IBM_TDB	
35	210	silicide.clm. same isolation.clm. same	USPAT;	2004/09/17
	210	(insulating or insulator or insulation or	US-PGPUB;	2004/09/1 <i>7</i> 22:16
		dielectric).clm.	EPO; JPO;	22i 10
			DERWENT;	
			IBM_TDB	

36	128	silicide.clm. same isolation.clm. same	USPAT;	2004/09/17
		(insulating or insulator or insulation or	US-PGPUB;	22:17
		dielectric).clm. and ((insulating or insulator	EPO; JPO;	
		or insulation or dielectric) with	DERWENT;	
		isolation).clm.	IBM_TDB	
37 38	52	silicide.clm. same isolation.clm. same	USPAT;	2004/09/17
		(insulating or insulator or insulation or	US-PGPUB;	22:17
		dielectric).clm. and ((insulating or insulator	EPO; JPO;	
	İ	or insulation or dielectric) with isolation	DERWENT;	
		with silicide).clm.	IBM_TDB	
	19	silicide.clm. same isolation.clm. same	USPAT:	2004/09/17
		(insulating or insulator or insulation or	US-PGPUB;	22:23
		dielectric).clm. and ((insulating or insulator	EPO; JPO;	
		or insulation or dielectric) with isolation	DERWENT;	
:		with silicide with (sidewall or spacer or	IBM_TDB	
		(side adj wall))).clm.		
39	15	silicide.clm. same isolation.clm. same	USPAT;	2004/09/17
		(insulating or insulator or insulation or	US-PGPUB;	22:24
		dielectric).clm. and ((insulating or insulator	EPO; JPO;	
		or insulation or dielectric) with isolation	DERWENT;	
		with silicide with (sidewall or spacer or	IBM_TDB	
		(side adj wall))).clm. and (isolation near10	15155	
		(insulating or insulation or insulator or		
		dielectric)).clm.		
40	3	silicide.clm. same isolation.clm. same	USPAT;	2004/09/17
••		(insulating or insulator or insulation or	US-PGPUB;	22:27
		dielectric).clm. and ((insulating or insulator	EPO; JPO;	22:21
	,	or insulation or dielectric) with isolation	DERWENT;	
		with silicide with (sidewall or spacer or		
		(side adj wall))).clm. and ((isolation near2	IBM_TDB	
		layer) near5 ((insulating or insulation or		
41	21	insulator or dielectric) near2 layer)).clm.	HODAT	0004/00/47
→ 1	21	(US-6781193-\$ or US-4738624-\$ or	USPAT;	2004/09/17
		US-5643821-\$ or US-5899742-\$ or	US-PGPUB	22:26
		US-5986312-\$ or US-6046103-\$ or		
		US-6225202-\$ or US-6265271-\$ or		
		US-6274420-\$ or US-6420770-\$ or		
]	US-6551927-\$ or US-6747328-\$).did. or		
		(US-20030030097-\$ or US-20040070034-\$ or		
		US-20030230779-\$ or US-20020022367-\$ or		,
		US-20020060365-\$ or US-20030036233-\$ or		•
		US-20030038320-\$ or US-20030049918-\$ or		
	1	US-20040175909-\$).did.		

42	4	((US-6781193-\$ or US-4738624-\$ or	USPAT;	2004/09/17
"		US-5643821-\$ or US-5899742-\$ or	US-PGPUB;	22:28
		US-5986312-\$ or US-6046103-\$ or	EPO; JPO;	
		US-6225202-\$ or US-6265271-\$ or	DERWENT;	
		US-6274420-\$ or US-6420770-\$ or	IBM_TDB	
		US-6551927-\$ or US-6747328-\$).did. or		
		(US-20030030097-\$ or US-20040070034-\$ or		
		US-20030230779-\$ or US-20020022367-\$ or		
		US-20020060365-\$ or US-20030036233-\$ or		
j		US-20030038320-\$ or US-20030049918-\$ or		
		US-20040175909-\$).did.) and ((isolation		
		near2 layer) near5 ((insulating or insulation		
	,	or insulator or dielectric) near2 layer)).clm.		
43	70	silicide.clm. and (sidewall or spacer).clm.	USPAT;	2004/09/17
43	/0	· · · · · · · · · · · · · · · · · · ·	1	
		and ((isolation near2 layer) near5	US-PGPUB;	22:30
		((insulating or insulation or insulator or	EPO; JPO;	
	İ	dielectric) near2 layer)).clm.	DERWENT;	
			IBM_TDB	
44	12	silicide.clm. with (sidewall or spacer).clm.	USPAT;	2004/09/17
		and ((isolation near2 layer) near5	US-PGPUB;	22:30
		((insulating or insulation or insulator or	EPO; JPO;	
		dielectric) near2 layer)).clm.	DERWENT;	
			IBM_TDB	
45	1	silicide.clm. with (sidewall or spacer).clm.	USPAT;	2004/09/17
		with ((isolation near2 layer) near5	US-PGPUB;	22:35
		((insulating or insulation or insulator or	EPO; JPO;	
		dielectric) near2 layer)).clm.	DERWENT;	
			IBM_TDB	
46	462	(silicide near10 gate).clm. and (silicide with	USPAT;	2004/09/17
		spacer with (insulating or dielectric or	US-PGPUB;	22:36
		insulation or insulator))	EPO; JPO;	
		,,	DERWENT;	
			IBM_TDB	
47	162	(silicide near10 gate).clm. and (silicide with	USPAT;	2004/09/17
		spacer with (insulating or dielectric or	US-PGPUB;	22:37
		insulation or insulator)).clm.	EPO; JPO;	
		,	DERWENT;	
			IBM_TDB	
48	21	(silicide near10 gate).clm. and (silicide with	USPAT;	2004/09/17
		(align or aligned or aligning or alignment)	US-PGPUB;	22:39
		with spacer with (insulating or dielectric or	EPO; JPO;	22.00
		insulation or insulator)).clm.	DERWENT;	
		mostation of mouldtorpicing.	· · · · · · · · · · · · · · · · · · ·	
49	13	(silicide near10 gate).clm. and (silicide with	IBM_TDB	2004/00/47
73	13	•	USPAT;	2004/09/17
		(source or drain or source/drain) with (align	US-PGPUB;	22:41
		or aligned or aligning or alignment) with	EPO; JPO;	
		spacer with (insulating or dielectric or	DERWENT;	
	L	insulation or insulator)).clm.	IBM_TDB	

50	7	(silicide near10 gate).clm. and (silicide with	USPAT;	2004/09/17
		(source or drain or source/drain) with (align	US-PGPUB;	22:44
		or aligned or aligning or alignment) with	EPO; JPO;	
		spacer with (insulating or dielectric or	DERWENT;	
		insulation or insulator)).clm. and	IBM_TDB	
	•	isolation.clm.		
51	0	(silicide near10 gate).clm. and (silicide with	USPAT;	2004/09/17
		(source or drain or source/drain) with (align	US-PGPUB;	22:43
		or aligned or aligning or alignment) with	EPO; JPO;	
		spacer with (insulating or dielectric or	DERWENT;	
		insulation or insulator)).clm. and	IBM_TDB	•
		isolation.clm. and (I near shaped)		
52	1	(silicide near10 gate).clm. and (silicide with	USPAT;	2004/09/17
		(source or drain or source/drain) with (align	US-PGPUB;	22:44
		or aligned or aligning or alignment) with	EPO; JPO;	
		spacer with (insulating or dielectric or	DERWENT;	
		insulation or insulator)).clm. and	IBM TDB	
		isolation.clm. and (block or blocking or		,
		blocked).clm.		